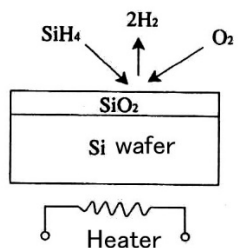
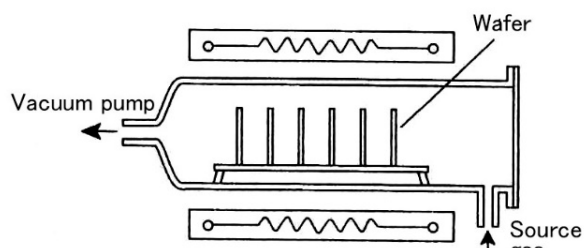


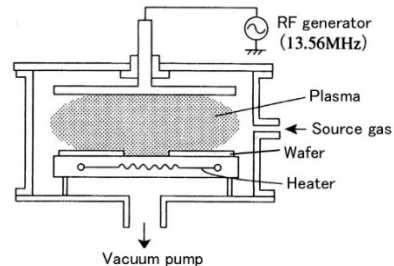
4 Chemical vapor deposition (CVD) and RF induction heating



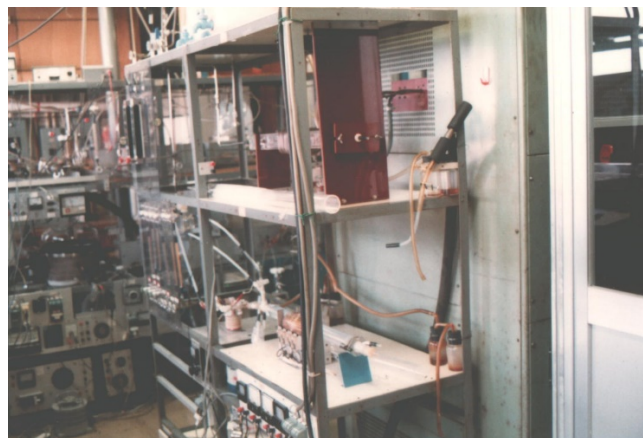
Principle of chemical vapor deposition



Low pressure (LP) CVD



Plasma CVD

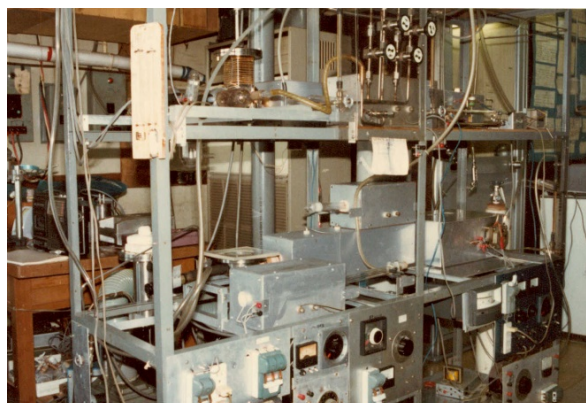
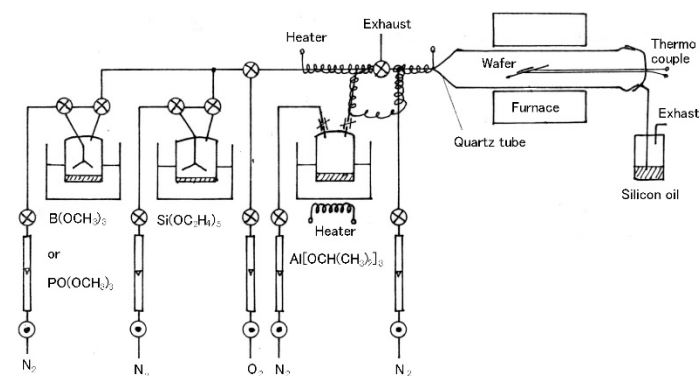


RF heating poly Si, SiO₂ CVD (top)

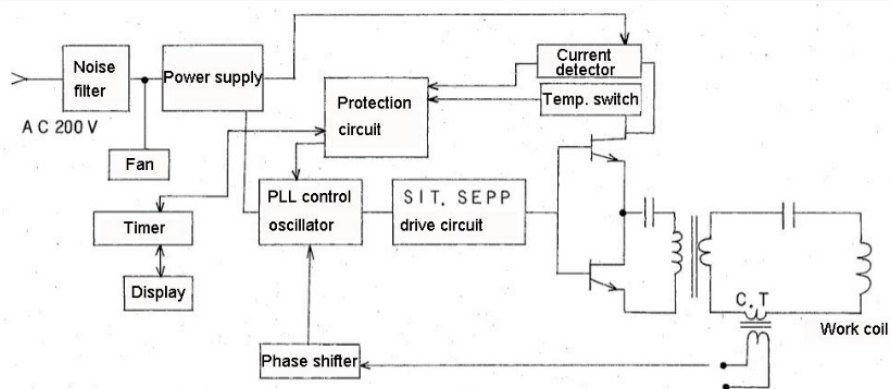
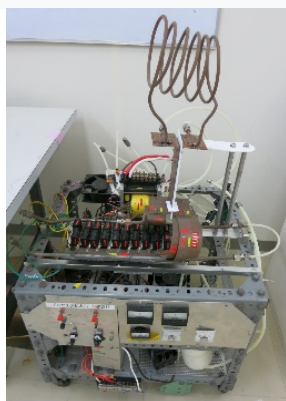
Infrared heating Al₂O₃, Ta₂O₅ CVD (bottom)



Low temperature SiO₂CVD (exhibited)



Organic liquid source (Tetraethoxysilane TEOS etc.) P₂O₅-SiO₂, B₂O₃-SiO₂, Al₂O₃-SiO₂ CVD



Oscillator for RF inductive heating using SIT (static induction transistor) (Token)(exhibited)